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ISSUE CL
Class

U.S. UTILITY Patent Application

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PATENT DATE

APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/729339	F	438	29	20018	Q. HOANG
APPLICANTS	Kyoichi Suwa				
TITLE	Mask, exposure method, line width measuring method, and method for manufacturing semiconductor devices				

PTO-2040
12/89

ISSUING CLASSIFICATION

Continued on Issue Slip Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
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	(Assistant Examiner)	(Date)			
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____				ISSUE FEE	
	(Primary Examiner)	(Date)		Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.				ISSUE BATCH NUMBER	
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